

A Commercial Laboratory Soft-X-ray Source for Water Window Microscopy

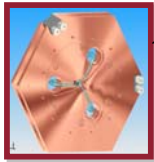
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ABSTRACT

Beginning in 2006, Energetiq Technology Inc. began development[1] of a soft x-ray source based on our commercially successful EUV source[2], based on a unique electrode-less Z-pinch design. Operating in Nitrogen, the source produces up to 400 mW of radiation at 2.88 nm. (430 eV)[3]. The source has been used as an illuminator for our own demonstration water-window microscope, and has been successfully integrated by Xradia, Inc. (Pleasanton, CA, USA) with their cryo-tomo-capable soft x-ray microscope, the UltraXRM-S/L220c. While laboratory demonstrations of microscopes driven by tabletop x-ray sources have been done [4, for instance], this is the first commercially available instrument of this type. We will present detailed performance data for the source.

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2005: First EQ-10; 10 W/2pi, 13.5 nm [1]



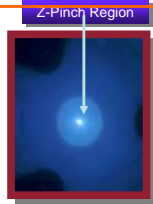
EQ-10 Concepts..

10 watts/2p, 13.5 nm,

+/- 1% bandwidth.

Xenon plasma.

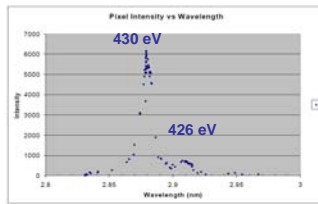
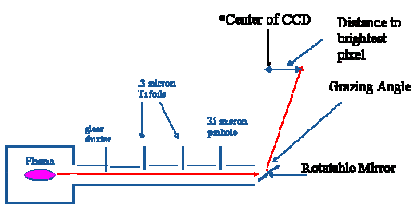
(Xe 10+)



Source developed (2005) to enable EUV lithography for semiconductor fabrication.

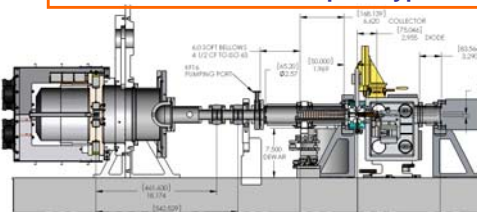
Further developments: [2,3]

2006: Phase 1 – explore various gases; power and spectral measurements.



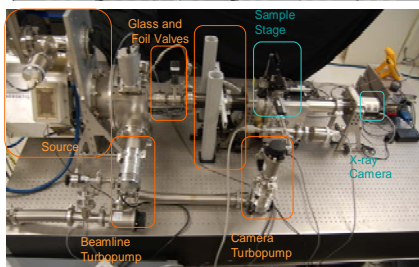
- Diagnostics developed. Several gasses tested; nitrogen selected: 430 eV from N5+. $\Delta\lambda/\lambda < 1/500$ Helium-like transition
- Plasma volume increased – compensate for molecular losses compared to Xenon. First power measurements ~ 200 mW/2 π

2007-2009 : Phase 2 - prototype microscope [4]

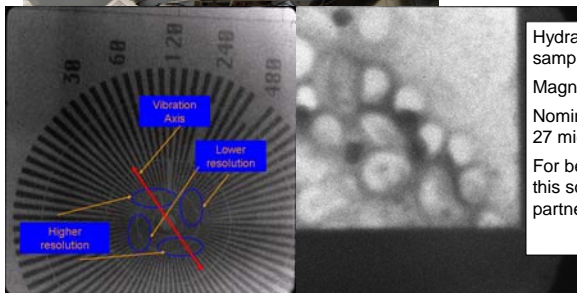


Partnered with Xradia, Inc. (Pleasanton, CA) to test on a commercial microscope as well as our prototype.

Spectral purity confirmed adequate via imaging



Since zone plate focal length varies with wavelength, line bandwidth can cause chromatic aberration. Resolution limits due to line bandwidth have not been seen. Resolution limit is better than 30 nm. (See Xradia results, this meeting.)



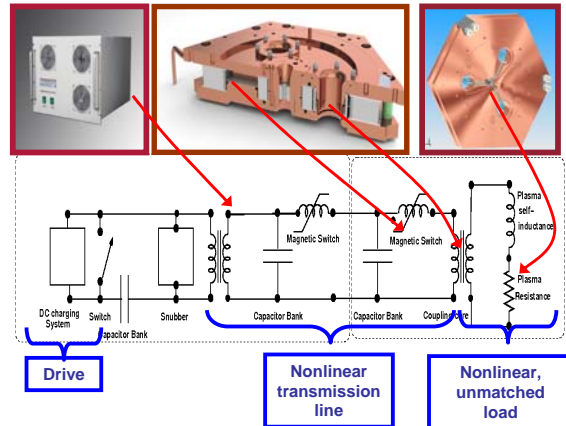
Hydrated yeast sample (not frozen). Magnification 484x Nominal field of view 27 microns For better photos with this source, see our partner, Xradia.

Ultimately, resolution was limited by drift and vibration. Achieved ~ 50 nm resolution on our microscope; ~ 40 nm resolution at Xradia.

2010-2011 Phase 2 Renewal: Cryo-Tomo results, Extensive testing, lifetime and maintenance improvements.

- Power system rebuilt - increased pulse energy, pulse rate
- Architctural modifications to manage higher voltage

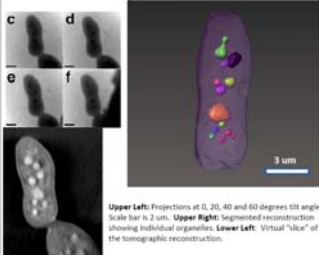
Simplified schematic diagram of power system and source.



2010: Cryo-tomography at Xradia

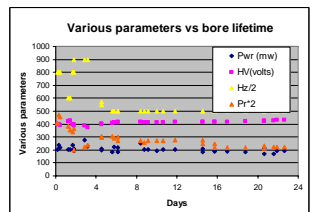
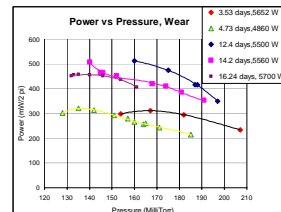
Experimental Results: Tomography of Frozen Hydrated Yeast

Sample preparation: Yeast cells were suspended in a PBS solution and applied to standard TEM grids, then plunge-frozen and transferred onto cartridges and into the microscope at cryogenic temperature. Total exposure time is approximately 6 hrs. Pixel size is 32 nm. Data submitted for publication.



- First cryo-tomographic results.
- Major effort to improve bore lifetime.
- Lifetime improved from ~ 5 days to ~ 20 days, at higher output power.
- Maintenance time (bore change, power to source) reduced from ~ 3 days to ~ 12 hrs

Power output to 400 mW; 20 day bore life achieved



2012: Installation at customer site (DiamondLight Source, UK)



References

- [1] Denbeaux, G., Naulleau, P., Horne, R. G. S., Besen, M., First use of the Energetiq 10w Electroless EUV Plasma source. In: 2005 International EUV Symposium, San Diego, CA.
- [2] Horne, S. F., Niall, F. M., Partlow, M. J., Besen, M. M., Smith, D. K., Blackborow, P. A., Gustafson, D., 2009. Development of a high-pulse-rate euv source. Vol. 7271. SPIE, pp. 72713A+.
- [3] Partlow, M., Besen, P., Blackborow, R., Collins, D., Gustafson, S., Horne, and D. Smith, "Extreme-ultraviolet light source development to enable pre-production mask inspection (journal paper)", 2012.
- [4] S. F. Horne, J. Siller, and W. Holber, "A compact soft x-ray microscope using an electrode-less z-pinch source," Journal of Physics: Conference Series, vol. 186, no. 1, pp. 012 028+, 2009. [Online]. Available: <http://dx.doi.org/10.1088/1742-6596/186/1/012028>

Acceptance testing onsite prior to connecting source to microscope